

## AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application.

Claims 1-57 (Cancelled)

58. (New) A set of masks comprising:

a first mask having a first pair of low and high transmittance phase shifting regions; and

a second mask having a second pair of low and high transmittance phase shifting regions, wherein the second pair is reversed relative to the first pair and a high transmittance phase shifting region of the second pair corresponds to a low transmittance phase shifting region of the first pair.

59. (New) The set of masks of claim 58, wherein the first pair is to expose a line, and wherein the second pair is to reduce a width of the line.

60. (New) The set of masks of claim 58, wherein at least one low transmittance phase shifting region of the first and second pairs comprises an arrangement of opaque subresolution shapes.

61. (New) The set of masks of claim 60, wherein at least one low transmittance phase shifting region of the first and second pairs comprises a grid of opaque subresolution shapes.

62. (New) The set of masks of claim 58, wherein at least one low transmittance phase shifting region of the first and second pairs comprises a layer or film that provides partial transmittance.

63. (New) The set of masks of claim 62, wherein the layer or film includes at least one of molybdenum silicide and chromium fluoride.
64. (New) The set of masks of claim 58, further comprising:  
  
a portion of the first mask to expose a feature in the radiation sensitive layer; and  
  
a portion of the second mask to add a structural feature to the exposed feature.
65. (New) The set of masks of claim 58, further comprising:  
  
a portion of the first mask to expose a feature in the radiation sensitive layer; and  
  
a radiation intensity reducer of the second mask to reduce a subwavelength distortion of the exposed feature.
66. (New) The set of masks of claim 58, further comprising:  
  
a first opaque line of the first mask to expose a line having a width in the radiation sensitive layer; and  
  
a second opaque line of the second mask to reduce the width of the exposed line.
67. (New) A set of masks comprising:  
  
a first mask having a first low transmittance region to transmit comparatively low intensity radiation to a radiation sensitive layer and a first high transmittance region to transmit comparatively high intensity radiation to the radiation sensitive layer; and  
  
a second mask having a second high transmittance region that corresponds to the first low transmittance region and a second low transmittance region that corresponds to the first high transmittance region.

68. (New) The set of masks of claim 67, wherein each of the low and high transmittance regions are phase shifting regions, and wherein the low and high transmittance phase shifting regions of the first mask are reversed relative to the low and high transmittance phase shifting regions of the second mask.
69. (New) The set of masks of claim 67, wherein at least one of the low transmittance regions comprises an arrangement of opaque subresolution shapes.
70. (New) The set of masks of claim 69, wherein the arrangement comprises a grid of opaque subresolution shapes.
71. (New) The set of masks of claim 67, wherein at least one of the low transmittance regions comprises a layer or film that provides partial transmittance.
72. (New) The set of masks of claim 71, wherein the layer or film includes at least one of molybdenum silicide and chromium fluoride.
73. (New) The set of masks of claim 67, wherein the first low and high transmittance regions are to expose a linewidth, and wherein the second low and high transmittance regions are to reduce a width of the linewidth.
74. (New) The set of masks of claim 67, further comprising:  
  
a portion of the first mask to expose a feature in the radiation sensitive layer; and  
  
a portion of the second mask to add a structural feature to the feature.
75. (New) The set of masks of claim 67, further comprising:  
  
a portion of the first mask to expose a feature in the radiation sensitive layer; and

a radiation intensity reducer of the second mask to reduce a subwavelength distortion of the feature.

76. (New) The set of masks of claim 67, further comprising:

a first opaque line of the first mask to expose a line having a width in the radiation sensitive layer; and

a second opaque line of the second mask to reduce the width of the line.